

RUHR-UNIVERSITÄT BOCHUM

# Multi-diagnostic experimental validation of 1d3v PIC/MCC simulations of low pressure RF CCPs in argon

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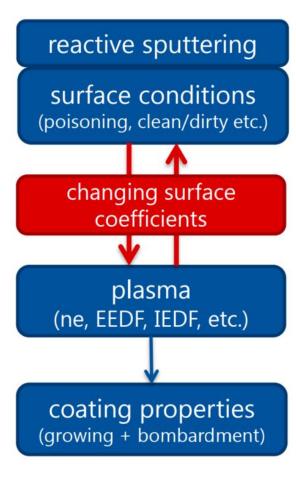
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<sup>&</sup>lt;sup>4</sup> Key Laboratory of Materials Modification by Laser, Ion and Electron Beams, School of Physics, Dalian University of Technology, China

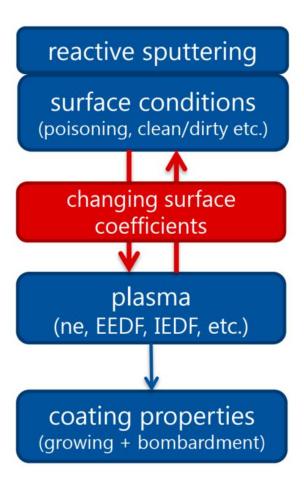
#### **Motivation**

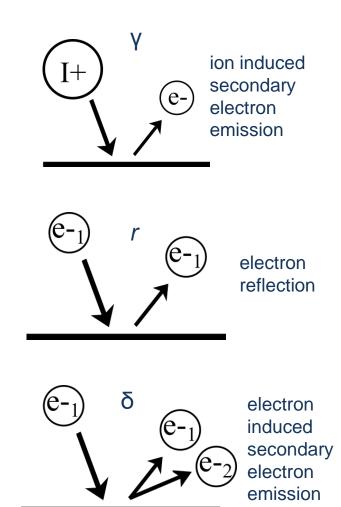






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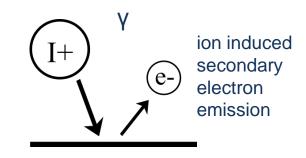


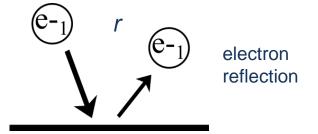


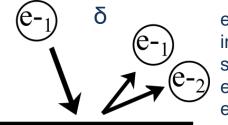
#### **Motivation**

reactive sputtering surface conditions (poisoning, clean/dirty etc.) changing surface coefficients plasma (ne, EEDF, IEDF, etc.) coating properties (growing + bombardment)

- Increasing demand for simulations with well known input parameters, especially surface coefficients
  - $\gamma(E)$ , r(E),  $\delta(E)$  not known under plasma conditions
  - especially sputtering: dirty process
  - coefficients must be obtained under these conditions
- → CCP reference cell in combination with PIC simulation
  - 1D simulation needs symmetric experiment for direct comparison
  - systematic, multi-diagnostic comparisonPIC <> experiment
- PIC (in this case):  $r_{\rm eff} = r + \delta = \frac{\text{\# of electrons leaving the surface}}{\text{\# of electrons reaching the surface}}$







electron
induced
secondary
electron
emission





### The experimental setup

#### The experimental setup – Photo and basic data

electrode gap: 40 mm

frequency: 13.56 MHz

voltage waveform: sine

voltage amplitudes: 150 V – 350 V

pressure: 1 Pa - 100 Pa

gas: Ar (5.0)

base pressure: ~5E-5 Pa

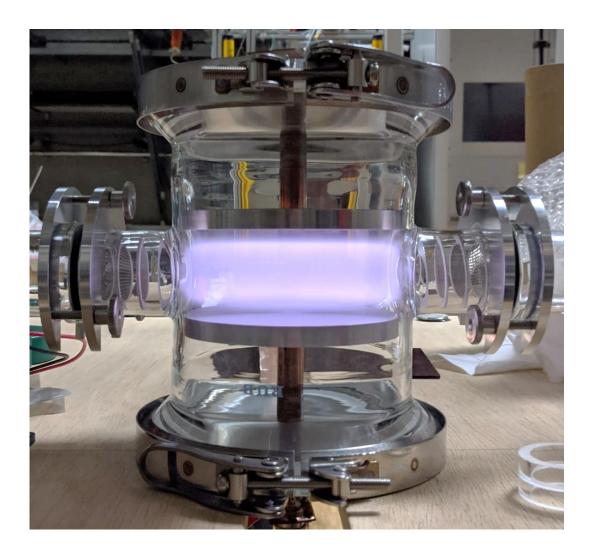
■ leakage rate: ~1E-4 sccm

gas flow: ~1 to 10 sccm

diagnostics:

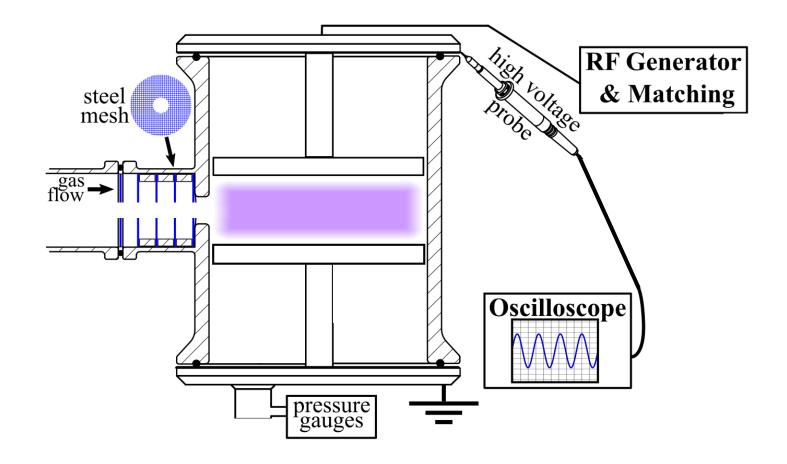
Phase resolved optical emission sprectroscopy (PROES)

- Langmuir probe
- Retrading field energy analyzer (RFEA)
- Tunable diode laser absorption spectroscopy (TDLAS)

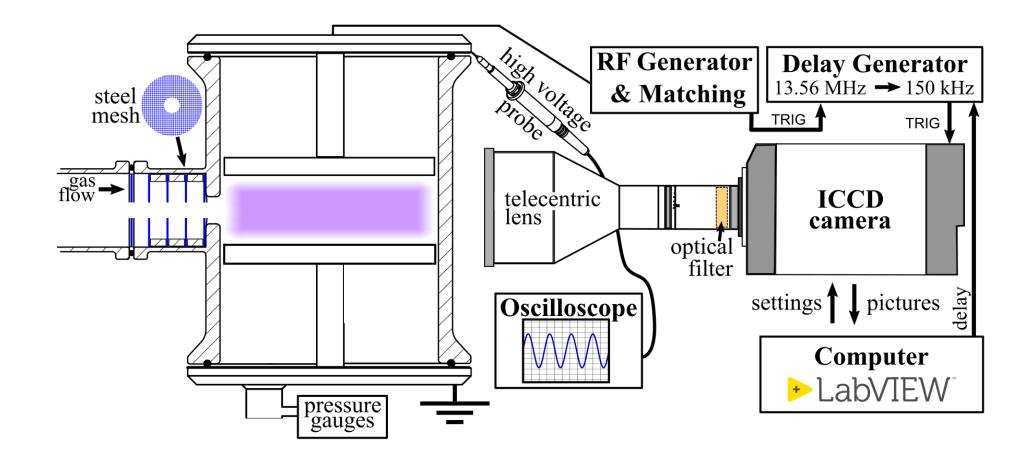






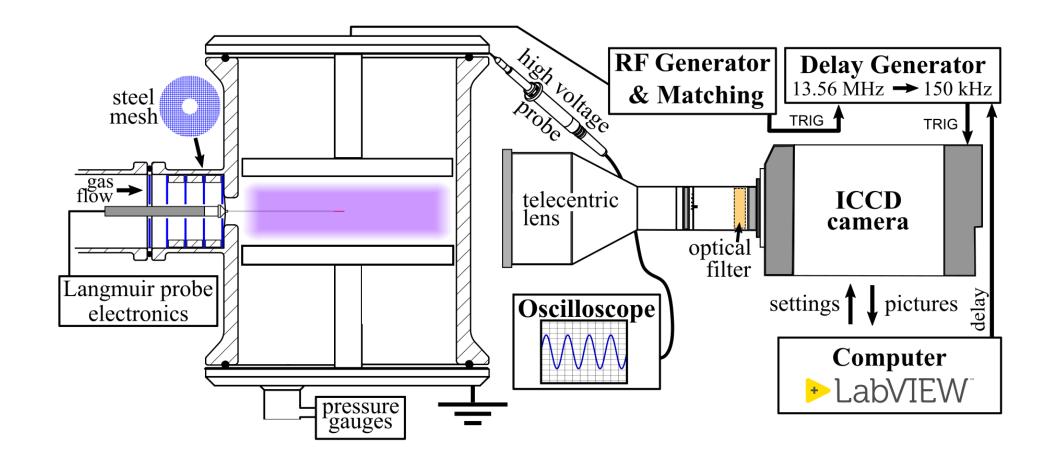






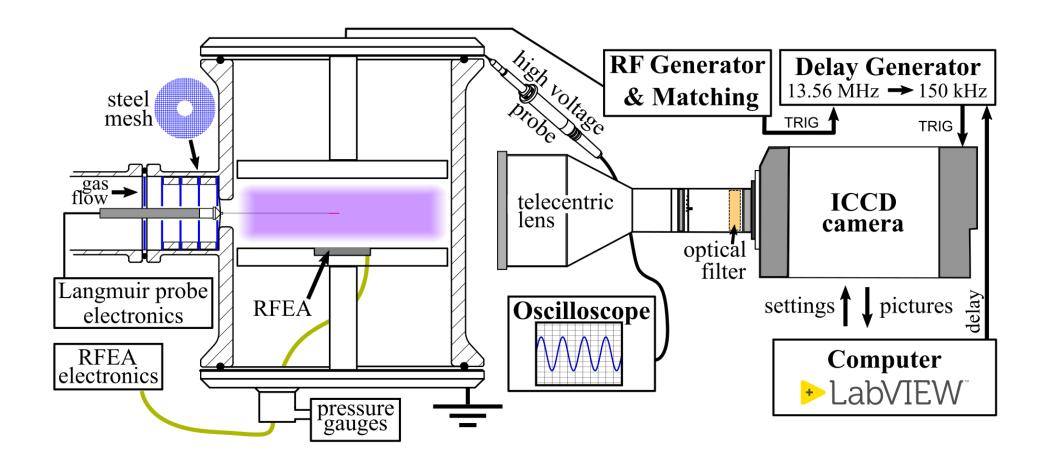






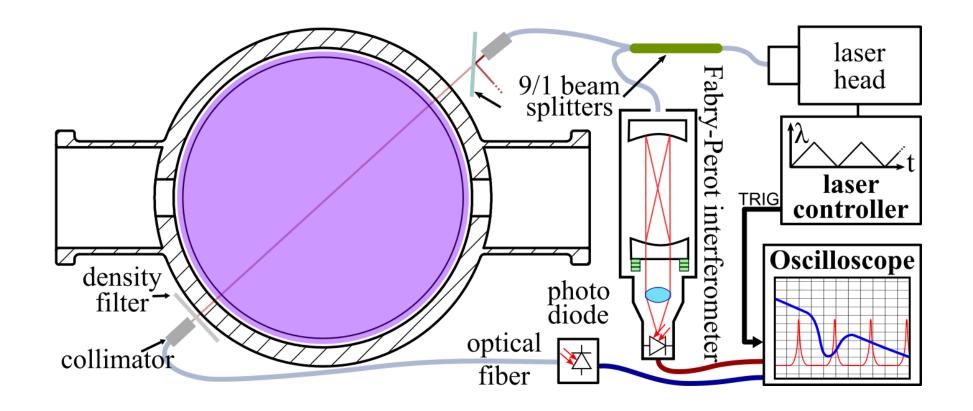












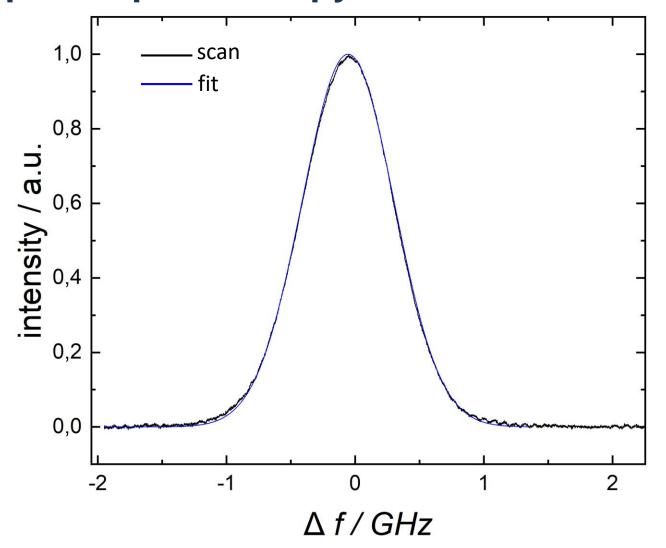




## Results: neutral gas temperature

#### **Tunable Diode Laser Absorption Spectroscopy**

- scan of an argon metastable absorption line (772.37 nm) with a tunable diode laser
- Scanned line has a gaussian shape due to doppler broadening
   → determination of temperature via gaussian fit
- Ar\* are not charged, therefor: metastable temperature = gas temperature

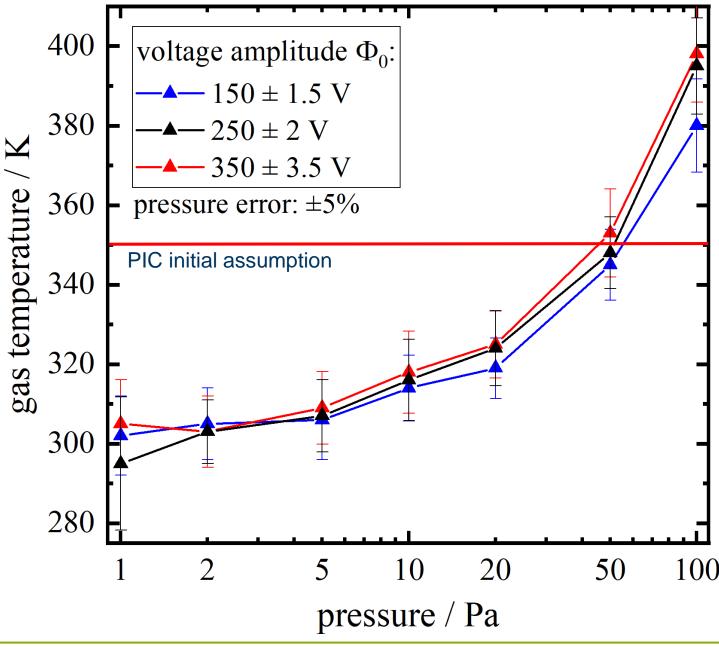






## The neutral gas temperature in the symm. CCP

- Gas temperature determined with TDLAS in the middle of the discharge
- Strongly pressure dependent
- Weakly driving voltage dependent for investigated conditions
- Initial assumption of constant 350 K is quite far off for most of the cases

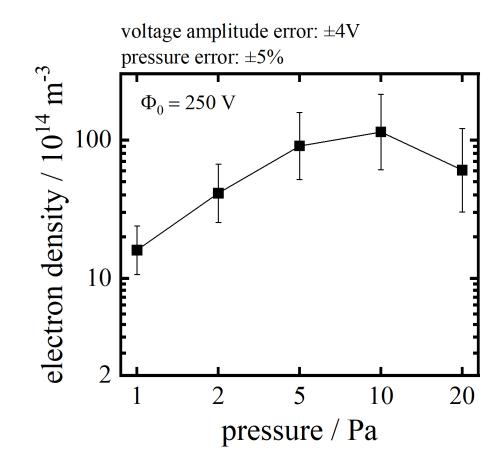






### Results: electron density

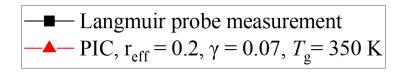
**■** Langmuir probe measurement

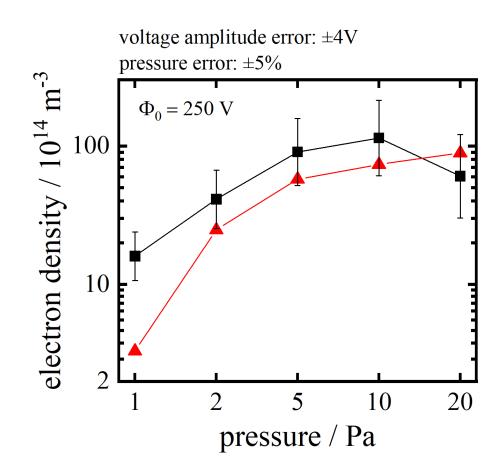






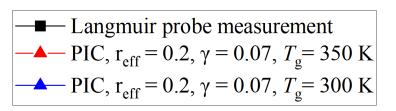
- experiment and simulation "base case" results agree well in the high-pressure range
- clear deviation at the lowest pressures



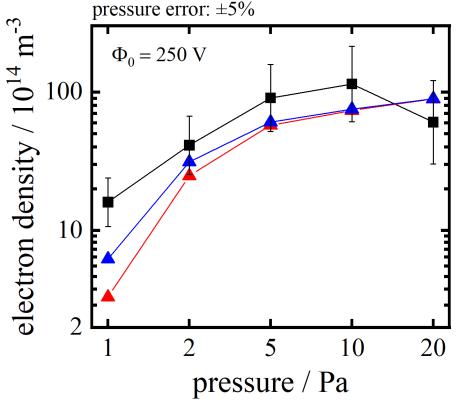




- experiment and simulation "base case" results agree well in the high-pressure range
- clear deviation at the lowest pressures
- lowering the gas temperature (PIC) increases the density



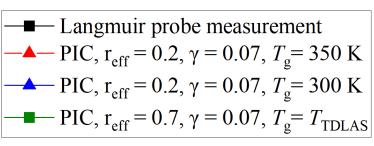
voltage amplitude error: ±4V



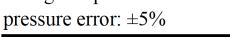


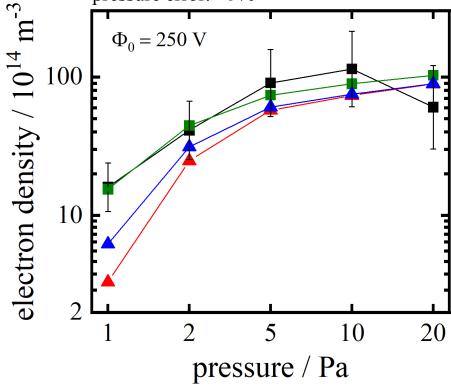
- experiment and simulation "base case" results agree well in the high-pressure range
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- lowering the gas temperature (PIC) increases the density
- simulation "best case":

$$r_{
m eff}=0.7$$
 ,  $\gamma=0.07$  ,  $T_{\it gas}=$  measured



voltage amplitude error: ±4V





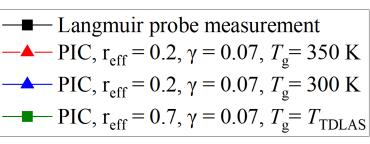


γ-value:

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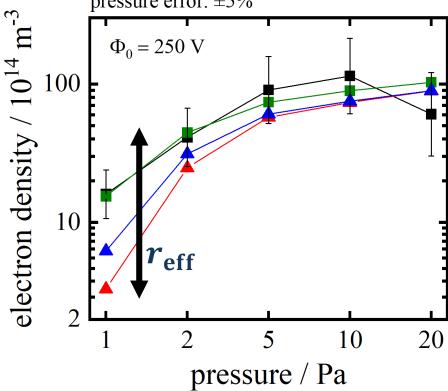
$$r_{
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• increasing  $r_{
m eff}$  increases the density at lower pressure more than at higher pressure



voltage amplitude error: ±4V

pressure error: ±5%

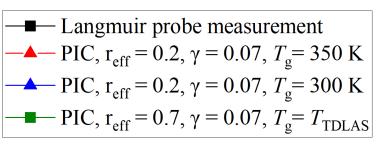




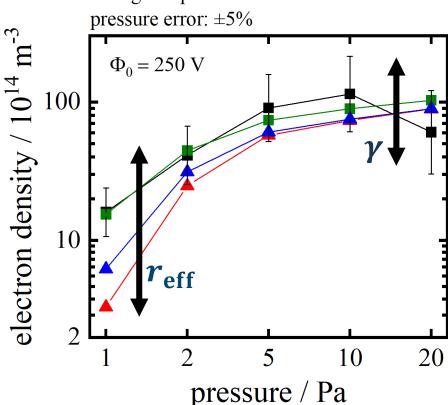
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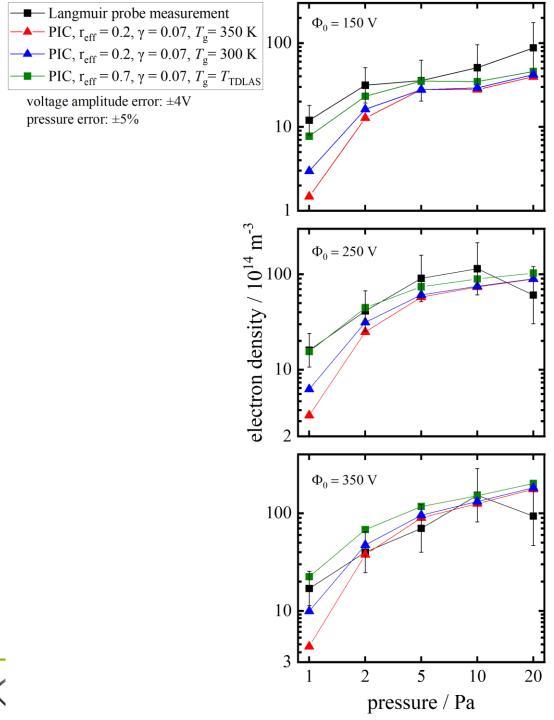




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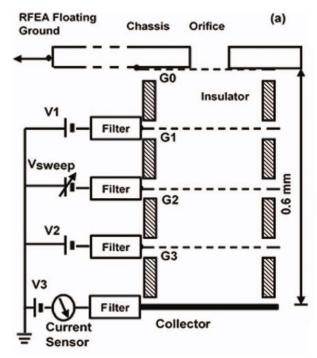
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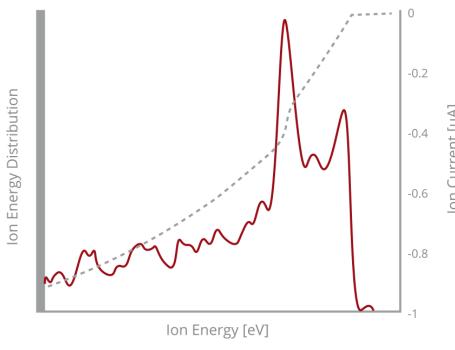
## Results: ion energy distribution function

#### **Retarding Field Energy Analyzer**

- stack of metal grids on selected potentials to let only ions reach the collector
- voltage sweep on G2 → limit energy of arriving ions
- derivative of ion current at the collector gives energy dependent ion flux



Schematic of the grid structure in the used RFEA. S. Sharma *et. al.*, Rev. Sci. Inst., vol. 85, no. 4, p. 043509, 2014



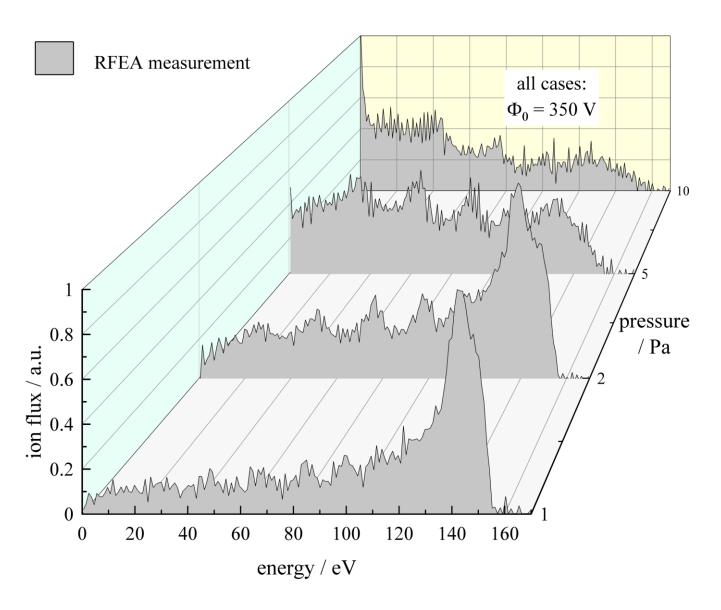
Example of typical RFEA measurement result: current-voltage-characteristic (grey dashed) and IEDF (red). Impedans Ltd., "THEORY OF OPERATION Semion System Retarding Potential Analyser"





#### **IEDFs:** pressure variation

high energy peak disappears with rising pressure due to more collisions

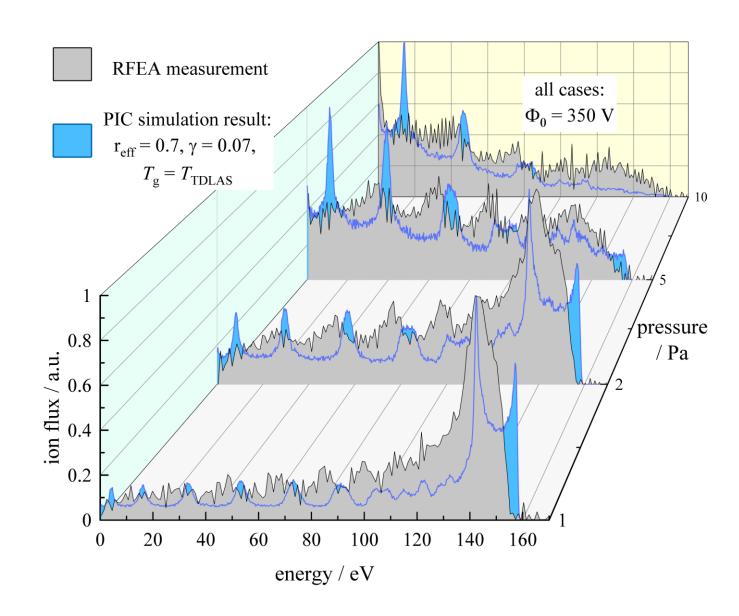






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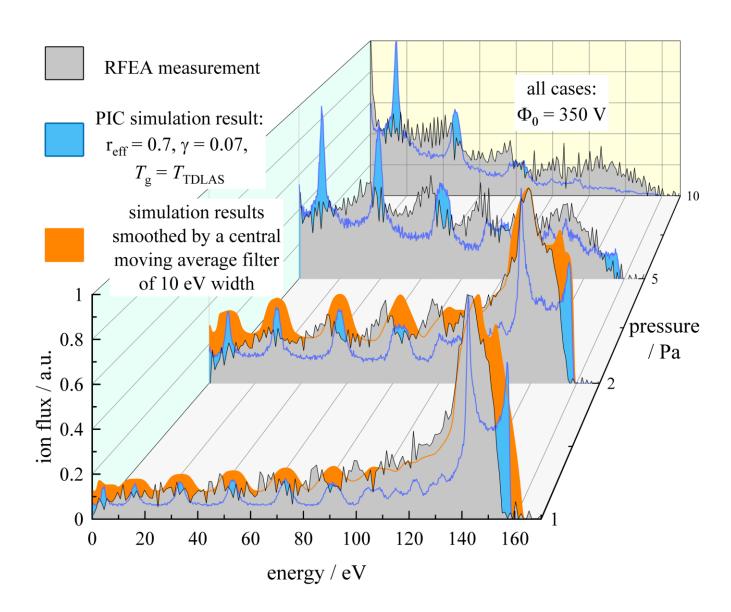
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- shift between experiment and simulation
- good agreement between number of simulated & measured peaks positions
- lowest peak at higher pressures can not be measured





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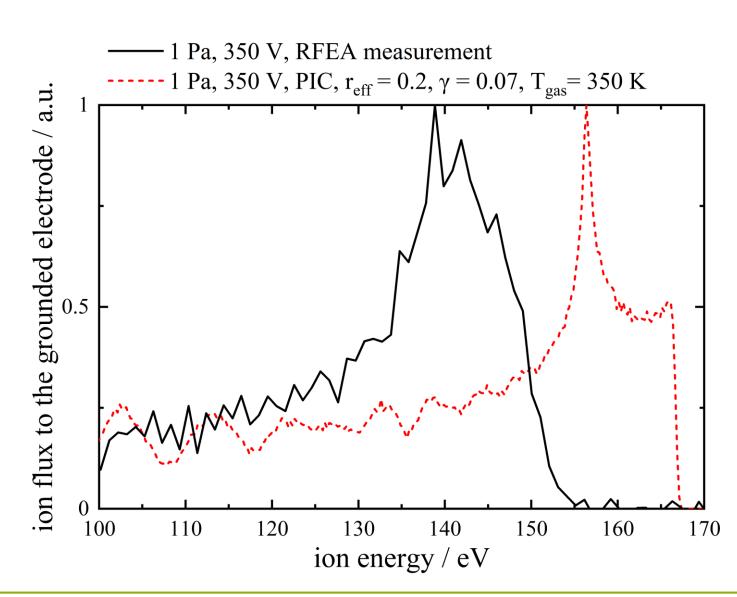
- high energy peak disappears with rising pressure due to more collisions
- shift between experiment and simulation
- good agreement between number of simulated & measured peaks positions
- lowest peak at higher pressures can not be measured
- resolution of the RFEA is ≠ grid voltage step(1 V)







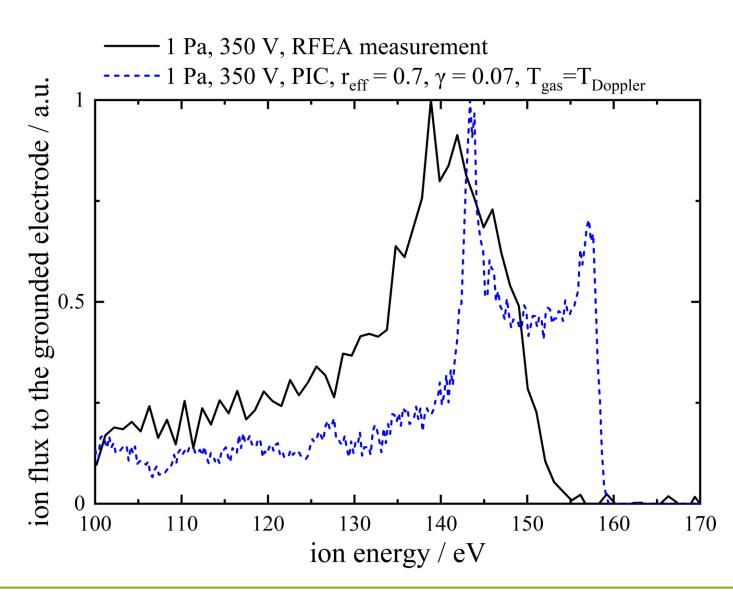
shift of ~20 eV between measurement and simulation base case







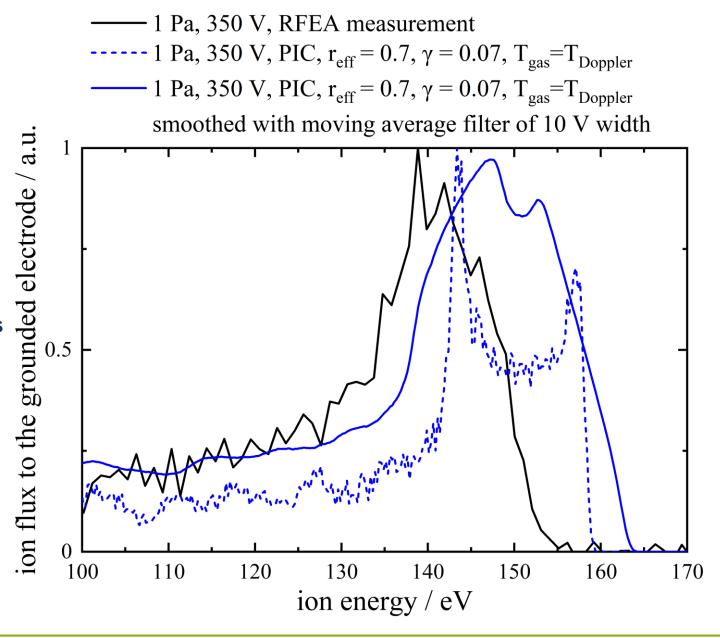
- shift of ~20 eV between measurement and simulation base case
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- double peak structure not visible in the measurement







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- double peak structure not visible in the
   measurement → RF noise pickup of RFEA cables







- shift of ~20 eV between measurement and simulation base case
- shift of ~10 eV between measurement and simulation best case
- double peak structure not visible in the measurement → RF noise pickup of RFEA cables

a.u.

100

110

120

grounded electrode / remaining shift can be explained by small DC self bias in experiment → correction results in ion flux to the excellent agreement regarding the position on the energy axis

1 Pa, 350 V, RFEA measurement, shifted by DC self bias 1 Pa, 350 V, PIC,  $r_{eff} = 0.7$ ,  $\gamma = 0.07$ ,  $T_{gas} = T_{Doppler}$ smoothed with moving average filter of 10 V width 0.5



ion energy / eV

140

150

160

130



170

## Results: spatio-temporal excitation

#### **Phase Resolved Optical Emission Spectroscopy**

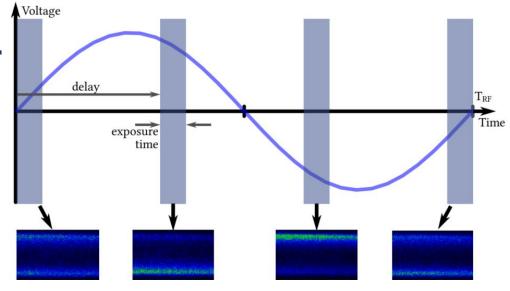
- measuring light at specific wavelength at specific points in time
- transitions are specifically chosen to be only produced by electron-impact excitation from the ground state
- de-excitation only via spontaneous emission
  - Ne 585.2 nm, lifetime 16 ns
  - Ar 750.4 nm, lifetime 22 ns
- calculation of relative excitation rate from measured emission
- excitation rate can also be calculated in PIC simulation





#### **Phase Resolved Optical Emission**

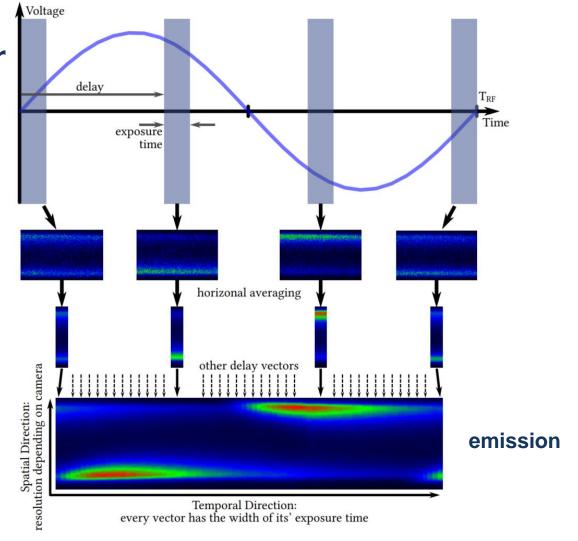
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   More info: J. Schulze et al., J. Phys. D. 43 (2010)

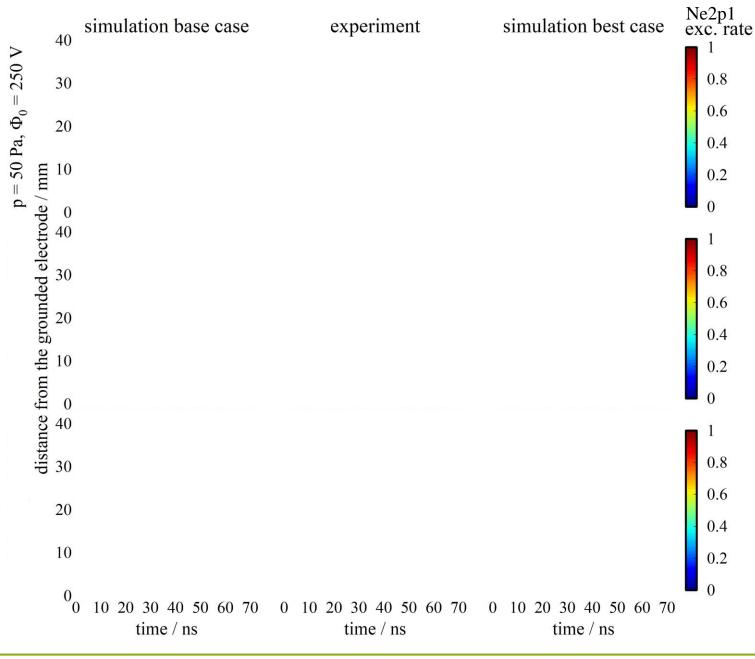
horizonal averaging other delay vectors emission Temporal Direction: every vector has the width of its' exposure time calculation of the exciation rate from the measured emission excitation Time

Voltage

delay

exposure time  $T_{RF}$ 

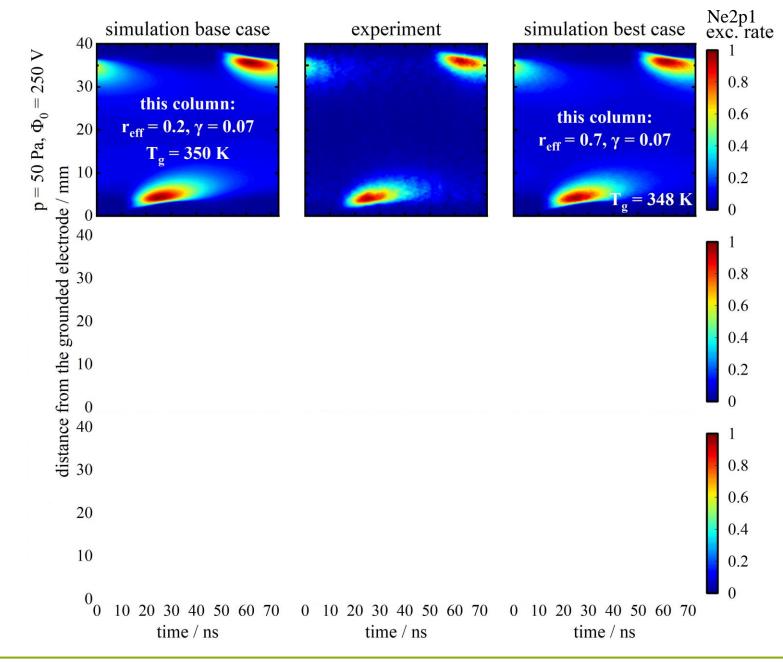
Time







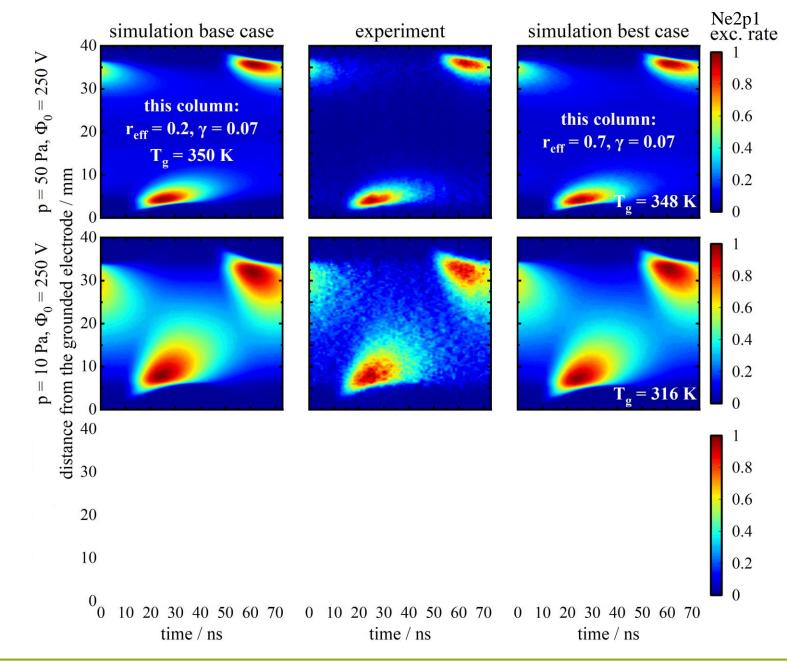
50 Pa: no visible differences







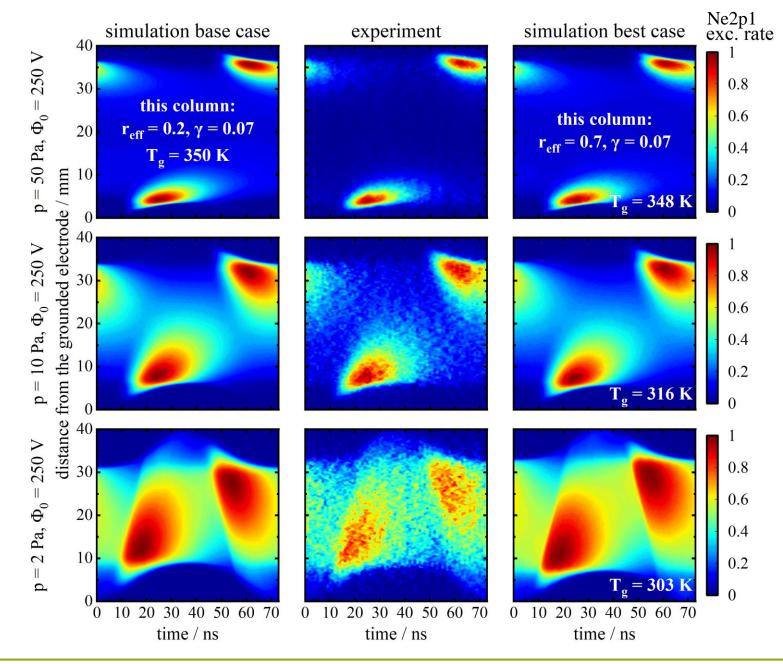
- 50 Pa: no visible differences
- 10 Pa: still no big differences







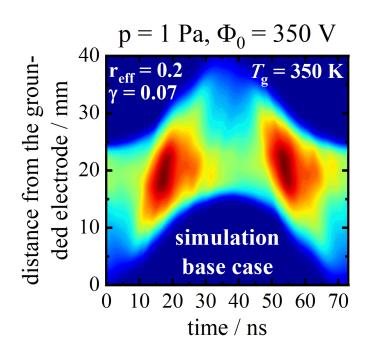
- 50 Pa: no visible differences
- 10 Pa: still no big differences
- 2 Pa: small differences in sheath width

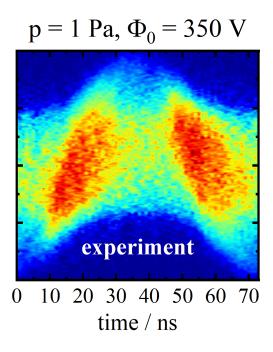






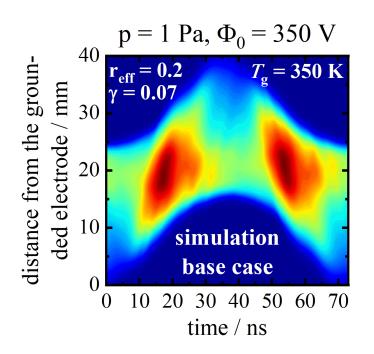
#### **Excitation rate comparison at 1 Pa**

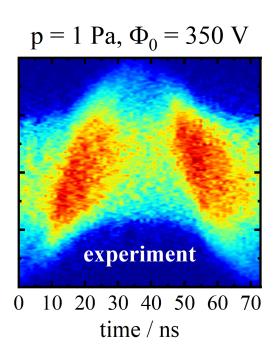


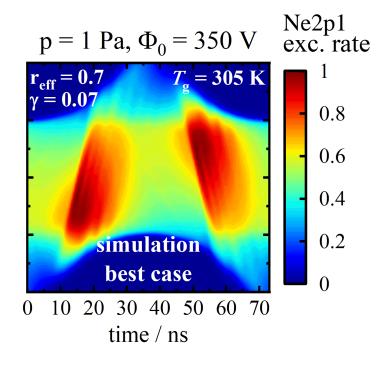




#### **Excitation rate comparison at 1 Pa**







- difference in sheath thickness between experiment and simulation for base case
- Increase of  $r_{\rm eff}$  and decrease of  $T_{\rm gas}$  decreases sheath thickness
- 2 Pa: much smaller difference
  - 1 Pa: electron mean free path > electrode gap
  - 2 Pa: electron mean free path < electrode gap</p>





#### **Summary**

- results from different diagnostics are consistent
- precise knowledge of the gas temperature is required for accurate simulation results
- $r_{\rm eff}$  for stainless steel is ~0.7
- Based on a systematic variation of pressure and voltage, surface coefficients can be determined!
- Acknowledgement: DFG: SFB-TR 87, Project C1
- Have a look:

"Multi-diagnostic experimental validation of 1d3v PIC/MCC simulations of low pressure capacitive RF plasmas operated in argon" (Accepted Manuscript), David Alexander Schulenberg, Ihor Korolov, Zoltán Donkó, Aranka Derzsi and Julian Schulze, PSST 2021, https://doi.org/10.1088/1361-6595/ac2222







#### Thank you for your attention!



